

ABSTRACT

Provided is an exposure device, comprising: a light source (1), an illuminating module (2), a mask table (5), a projection objective lens module, an imaging position adjustment module (4) and a workpiece table (6) provided consecutively along the transmission direction of an optical path. The imaging position adjustment module (4) comprises a plurality of adjustment units (410) provided separately. The projection objective lens module comprises a plurality of projection objective lenses (3). The position of the plurality of adjustment units (410) is in one-to-one correspondence with the imaging field of the plurality of projection objective lenses (3). The imaging position adjustment module (4) ensures the imaging quality of the projection objective lens module and the splicing quality of the projection objective lenses (3) by adjusting the performance, such as translation, magnification and focal plane, of the image generated by the projection objective lens module. The projection objective lens module does not have any imaging position adjustment elements or adjustment mechanisms, thus reducing the complexity of the projection objective lens module.